

ABSTRACT

An unnecessary film removal device, an unnecessary film removal method, and a method of manufacturing a photomask blank, the unnecessary film removal device wherein a shield member (cover member) is installed apart a specified distance from the surface of a substrate so that chemicals are not fed to the portions where film is required, and a chemical guide member is installed on the outside of the shield member (cover member) so that the chemicals are fed to the peripheral edge parts of the substrate. On the shield member (cover member), a distance adjusting member for adjusting the distance thereof from the principal surface of the substrate is installed at three or more positions. The installation positions of the distance adjusting members are so arranged not to be disposed in a straight line when the installation positions are connected to each other with a straight line, and when the shield member (cover member) is rotated by a specified angle relative to the substrate about the surface center of the substrate, not to be overlapped with the installation positions of the distance adjusting members before the rotation, or a moving mechanism is installed in the distance adjusting members.